

SEP. 10 2007

Docket No.: 020732-97.668 (7493)

Appl. No. 10/792,038

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:

Docket No.: 020732-97.668
(7493)

Applicants: RATH, Melissa K., et al.

Conf. No.: 4823

Application No.: 10/792,038

Art Unit: 1752

Date Filed: March 3, 2004

Examiner: LE, Hoa Van

Title: COMPOSITION AND PROCESS FOR POST-ETCH REMOVAL OF PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL DEPOSITED ON A SUBSTRATE

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Attn: Examiner Hoa Van Le

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Number of Pages (including cover)

Tristan A. Fuierer

September 10, 2007

Date _____

**AMENDMENT RESPONDING TO JULY 9, 2007 OFFICE ACTION AND SUPPLEMENTAL
INFORMATION DISCLOSURE STATEMENT IN UNITED STATES PATENT
APPLICATION NO. 10/792,038**

**Mail Stop AF
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450**

Sir:

This responds to the July 9, 2007 Office Action in the above-identified application.